

CLAIMS

1. A method for the manufacture of a device that includes the following steps:
 - (a) Formation of a base body (1) with two external electrodes opposite each other,
 - (b) Adjustment of the resistance of the base body (1) measured between the external electrodes to a given target value by means of chemical etching of portions of the base body.
2. The method according to Claim 1, wherein a base body (1) is utilized, which contains a ceramic material.
3. The method according to Claims 1 or 2, wherein a base body (1) is utilized, whose ohmic resistance has a negative temperature coefficient.
4. The method according to Claims 1 through 3, wherein a base body (1) is utilized whose smallest dimension (d) is less than 3 mm.
5. The method according to Claims 1 through 4, wherein the etching is carried out by dipping the base body (1) into a liquid that etches the base body (1).
6. The method according to Claim 5, wherein sulfuric acid is used as etching liquid.
7. The method according to one of Claims 1 through 6, wherein the actual value of the resistance of the base body (1) is measured before step (b).
8. The method according to Claim 7,

wherein during the etching the resistance (R25) of the base body is measured.

9. The method according to Claims 1 through 8,
- wherein before step (b) the difference between the target value and the actual value of the resistance (R25) is determined, whereas a duration (t) for the etch process is determined from said difference, and
 - wherein in step (b) the base body (1) is etched for the so determined etch duration (t).